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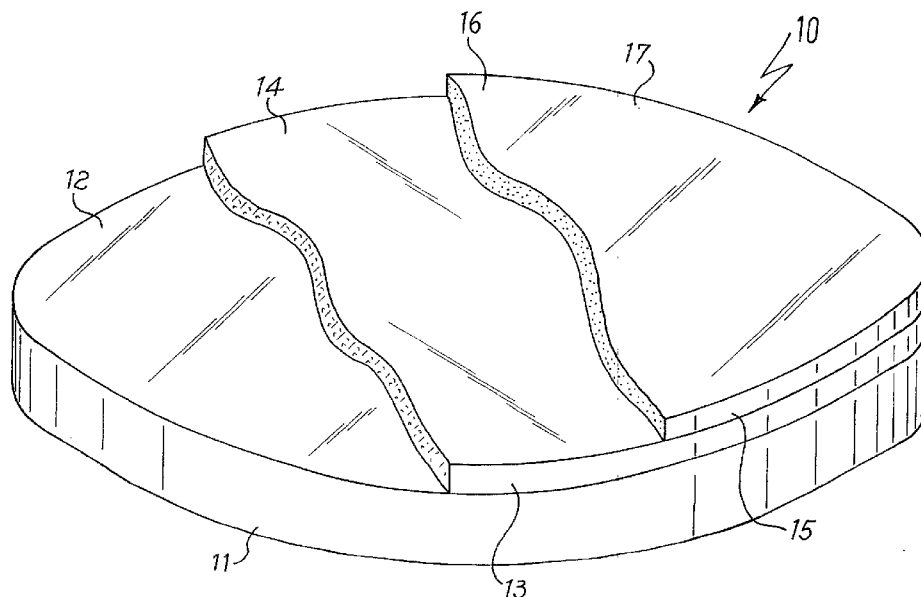
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(54) Title: SUPPORT WITH INTEGRATED DEPOSIT OF GAS ABSORBING MATERIAL FOR MANUFACTURING MICROELECTRONIC, MICROOPTOELECTRONIC OR MICROMECHANICAL DEVICES



(57) Abstract: It is described in different embodiments thereof a support (10; 20) for manufacturing microelectronic, microoptoelectronic or micromechanical devices requiring gas absorption for their correct operation, comprising a mechanical supporting base (11; 21), a layer (13) of a gas absorbing material on the base and a layer for temporary protection of the gas absorbing material, that is removed during the manufacture of the devices.



WO 03/009317 A3